

1 **Growth of ferromagnetic Fe₄N epitaxial layers and *a*-axis-oriented**
2 **Fe₄N/MgO/Fe magnetic tunnel junction on MgO(001) substrates using**
3 **molecular beam epitaxy**

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5 A. Narahara, K. Ito and T. Suemasu

6 *Institute of Applied Physics, University of Tsukuba, Tsukuba Ibaraki 305-8573, Japan*

7 **Abstract**

8 *a*-axis-oriented 80-nm-thick γ' -Fe₄N films were epitaxially grown on MgO(001)
9 substrates by supplying the Fe and N sources on the pre-deposited *a*-axis-oriented
10 30-nm-thick α -Fe epitaxial film. This technique has been used to form highly *a*-axis-oriented
11 Fe₄N(75 nm)/MgO(1 nm)/Fe(100 nm) magnetic tunnel junctions (MTJ)s from the Fe(7
12 nm)/MgO(1 nm)/Fe(100 nm) on the MgO(001) substrate. Magnetization versus the magnetic
13 field curve of the MTJ was measured at 280 K, and a two-step hysteresis loop was clearly
14 observed. This observation shows that the two ferromagnetic layers were separated by a
15 1-nm-thick MgO barrier.

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19 SQUID

20 **1. Introduction**

21 Spintronics, an emerging area in electronics, which is based on the combination of
22 magnetic and semiconducting materials, has attracted significant attention in recent years. The
23 tunnel magnetoresistance (TMR) effect in magnetic tunnel junctions (MTJs), which consists
24 of two ferromagnetic layers separated by an insulating layer, has also been extensively studied
25 [1, 2]. One way to realize a large TMR ratio is to grow a MTJ using a crystalline barrier, in
26 which coherent electron tunneling without spin scattering may be expected [3, 4]. Another
27 way involves the use of highly spin-polarized ferromagnetic materials such as electrodes [5,
28 6]. Thus, numerous different types of half metals and hetero junctions have been studied
29 extensively.

30 Iron nitrides have attracted significant attention as spintronic materials. These
31 materials have unique features including high-hardness, chemical inertness, and high
32 electrical conductivity. Among them, ferromagnetic α'' -Fe₁₆N₂, γ' -Fe₄N and ϵ -Fe₂₋₃N have
33 been extensively studied for applications in high-density magnetic recording heads and media
34 [7-17]. We have succeeded in the epitaxial growth of ϵ -Fe₃N on Si(111) [18], as well as the
35 formation of highly-oriented nitride-based crystalline Fe₃N/AlN/Fe₄N MTJs by molecular
36 beam epitaxy (MBE) using iron-pentacarbonyl (Fe(CO)₅) as an Fe source and nitrogen radical
37 beams produced by electron cyclotron resonance (ECR) plasma [19]. Kokado *et al.*
38 theoretically predicted highly spin-polarized transport in γ' -Fe₄N, therefore, this iron nitride

39 has attracted significant attention [20]. Recently, an inverse TMR effect was reported in
40 $\text{Fe}_4\text{N}/\text{MgO}/\text{CoFeB}$ MTJ that was fabricated by sputtering [21]. However, high-spin
41 polarization has not yet been reported for γ' - Fe_4N . Therefore, we expect that γ' - Fe_4N films are
42 a good candidate. The epitaxial growth of γ' - Fe_4N films has been reported by various growth
43 techniques including; reactive sputtering in ambient NH_3 [10], ion-beam assisted evaporation
44 [11], MBE of iron in the presence of an atomic nitrogen produced by radio-frequency plasma
45 [12, 13], halide vapor phase epitaxy using $\text{Fe}(\text{Cl})_3$ and NH_3 [14]. However, there have only
46 been a limited number of papers on the epitaxial growth of γ' - Fe_4N films [12-14].
47 Furthermore, there have been no reports on the growth of $\text{Fe}_4\text{N}/\text{MgO}/\text{Fe}_4\text{N}$ MTJs.

48 Herein, we report the epitaxial growth of γ' - Fe_4N films by a simple method, that is,
49 by nitriding the predeposited *a*-axis-oriented α -Fe epitaxial layers on $\text{MgO}(001)$ using
50 ECR- N_2 and $\text{Fe}(\text{CO})_5$. The highly *a*-axis-oriented $\text{Fe}_4\text{N}/\text{MgO}/\text{Fe}$ MTJ was also formed using
51 this technique. The probable method of formation of $\text{Fe}_4\text{N}/\text{MgO}/\text{Fe}_4\text{N}$ MTJ and the magnetic
52 properties of the γ' - Fe_4N films as well as the MTJ are discussed.

53

54 **2. Experimental procedures**

55 γ' - Fe_4N films and $\text{Fe}_4\text{N}/\text{MgO}/\text{Fe}$ MTJ were prepared by MBE using $\text{Fe}(\text{CO})_5$ as a Fe
56 source and a nitrogen radical beam produced by ECR plasma as follows. In the case of
57 γ' - Fe_4N films, first, *a*-axis-oriented 30-nm-thick α -Fe layers were epitaxially grown at 450 °C

58 using $\text{Fe}(\text{CO})_5$ on an $\text{MgO}(001)$ substrate after cleaning the substrate at $900\text{ }^\circ\text{C}$ for 60 min in
59 an ultra high vacuum. Then, the $\text{Fe}(\text{CO})_5$ and ECR-N_2 were supplied simultaneously at $450\text{ }^\circ\text{C}$
60 on the $\alpha\text{-Fe}$ layers. During growth, the $\alpha\text{-Fe}$ layers were nitrided to form $\gamma'\text{-Fe}_4\text{N}$. As a control,
61 a sample formed by supplying the Fe and N sources on a thinner $\alpha\text{-Fe}$ layer (7 nm) was
62 prepared. In addition, a sample formed by supplying only the N source was prepared. In the
63 case of $\gamma'\text{-Fe}_4\text{N}$ MTJ, the $\text{Fe}(\text{CO})_5$ and ECR-N_2 were supplied simultaneously at $450\text{ }^\circ\text{C}$ on the
64 a -axis-oriented $\text{Fe}(7\text{ nm})/\text{MgO}(1\text{ nm})/\text{Fe}(100\text{ nm})/\text{MgO}$ structure. During growth, the upper
65 $\alpha\text{-Fe}$ layers were nitrided to form the $\gamma'\text{-Fe}_4\text{N}$ and a 75-nm- Fe_4N film was grown. The
66 crystallinity of the grown layers was characterized by θ - 2θ X-ray diffraction (XRD) and
67 reflection high-energy electron diffraction (RHEED). All the RHEED patterns were taken
68 from the [100] azimuth of MgO. A superconducting quantum interference device (SQUID)
69 magnetometer was used to measure the magnetic properties of the samples.

70

71 **3. Results and discussion**

72 Figure 1(a) shows the θ - 2θ XRD pattern of the 30-nm-thick $\alpha\text{-Fe}$ layers on
73 $\text{MgO}(001)$. Together with the inserted RHEED pattern, the a -axis-oriented $\alpha\text{-Fe}$ film was
74 epitaxially grown. Since the lattice constant of MgO (0.421 nm) is almost the same as that of
75 $\alpha\text{-Fe}$ (0.287 nm) multiplied by $\sqrt{2}$, the a -axis-oriented $\alpha\text{-Fe}$ is rotated by 45° on $\text{MgO}(001)$
76 as shown in Fig. 2(a), that is; $\alpha\text{-Fe}(100)//\text{MgO}(001)$ with $\alpha\text{-Fe}[010]$ or $[001]//\text{MgO}[110]$.

77 Figures 1(b)-1(e) are the θ -2 θ XRD patterns of the samples obtained after 8, 15, 25 and 30
78 min. The peak intensity of α -Fe(200) decreased gradually with increasing the growth duration,
79 and almost disappeared after 30 min. In contrast, the peak intensity of γ' -Fe₄N(200) increased
80 and the thickness of γ' -Fe₄N became approximately 80 nm after 30 min, suggesting that the
81 *a*-axis-oriented α -Fe layer was nitrated to become *a*-axis-oriented γ' -Fe₄N. The diffraction
82 peak of α -Fe(200) disappeared completely after 60 min in the case of the thinner α -Fe layer
83 (7 nm), as shown in Fig. 1(f). The spotty RHEED pattern of γ' -Fe₄N shown in Fig. 1(e)
84 suggests that the epitaxial orientation of γ' -Fe₄N on MgO(001) can be explained by Fig. 2(b);
85 that is Fe₄N(100)//MgO(001) with Fe₄N[010] or [001]//MgO[100]. It is important to note that
86 after several minutes, as shown in Figs. 1(b) and 1(c), the diffraction peak of γ' -Fe₄N emerged.
87 In addition, the diffraction peak of γ' -Fe₄N was too weak to be seen as shown in Fig. 1(g),
88 when only the N source was supplied to the Fe/MgO. These results indicate that the
89 transformation of the predeposited α -Fe layers into γ' -Fe₄N occurs gradually in the surface
90 region of the α -Fe. This layer is then likely to work as a template for the overlayers, directing
91 the reaction of Fe and N sources to form γ' -Fe₄N layers. This results in the sudden increase in
92 XRD intensity of γ' -Fe₄N, as shown in Fig.1(c).

93 Figure 3 shows the magnetization versus magnetic field (*M-H*) curve measured for
94 the Fe₄N(80 nm)/MgO sample at 280 K. The external *H* was applied parallel to the sample
95 surface. The coercive field, *H_c*, is approximately 250 Oe. The saturation magnetization, *M_s*,

96 was deduced from the M - H curve to be approximately 1470 emu/cm^3 . This value is in good
97 agreement with that of bulk γ' - Fe_4N [22]. Spin polarization of the γ' - Fe_4N epitaxial layers is
98 now under evaluation by Andreev reflection measurements.

99 Figures 4(a) and 4(b) show the θ - 2θ XRD patterns of samples obtained (a) before
100 growth ($\text{MgO}(1 \text{ nm})/\text{Fe}(100 \text{ nm})/\text{MgO}(001)$ sub.) and (b) after 60 min of simultaneous supply
101 of Fe and N sources to the a -axis-oriented α - $\text{Fe}(7 \text{ nm})$ layer on the $\text{MgO}/\text{Fe}/\text{MgO}$. The
102 diffraction peaks of α - $\text{Fe}(200)$ and γ' - $\text{Fe}_4\text{N}(200)$ were clearly observed in Fig. 4(b), showing
103 that the a -axis-oriented MTJ was formed. The results shown in Fig. 1, indicate that the
104 7-nm-thick α - Fe layer was entirely transformed into γ' - Fe_4N layers. Furthermore, the peak
105 intensity of α - $\text{Fe}(200)$ in Fig. 4(b) became approximately half of that of Fig. 4(a). Thus, we
106 speculate that the upper region of the Fe layer on the bottom was likely to transform into
107 γ' - Fe_4N , indicating probable formation of $\text{Fe}_4\text{N}/\text{MgO}/\text{Fe}_4\text{N}$ MTJ. Previously, we reported the
108 formation of $\text{Fe}_3\text{N}/\text{AlN}(2 \text{ nm})/\text{Fe}_4\text{N}$ MTJ when the same Fe and N sources were supplied to
109 form ε - Fe_3N layers on the $\text{AlN}(2 \text{ nm})/\text{Fe}(30 \text{ nm})$ structure [19]. Rutherford backscattering
110 spectroscopy measurements revealed that the Fe layer was nitrified to form γ' - Fe_4N through
111 the 2-nm-thick AlN barrier layer during growth of the ε - Fe_3N layers. We speculate that a
112 similar event may occur in the current work.

113 Figure 5 shows the M - H curve measured for the MTJ at 280 K. The external H was
114 applied parallel to the sample surface. A clear two-step hysteresis loop can be observed, which

115 is typical for MTJs. This may be attributed to the difference in H_c between the top and bottom
116 ferromagnetic layers, showing successful formation of the two ferromagnetic layers separated
117 by the MgO barrier layer. The M_s values were well explained by the bulk γ' -Fe₄N and α -Fe.
118 The H_c values are 200 and 40 Oe, and originate from the top γ' -Fe₄N and the bottom α -Fe
119 layers, respectively. However, the possible formation of very thin layers of γ' -Fe₄N between
120 the MgO barrier layer and the bottom α -Fe layer cannot be ruled out. Therefore, further
121 studies are necessary in order to determine what actually occurs in the bottom α -Fe layer.

122

123 **4. Conclusions**

124 *a*-axis-oriented 80-nm-thick γ' -Fe₄N epitaxial layers were grown on MgO(001)
125 substrates by MBE using Fe(CO)₅ as a Fe source and ECR-N₂ as an N source. When the Fe
126 and N sources were supplied at 450 °C on the *a*-axis-oriented α -Fe layer, the Fe layer was
127 entirely nitrided to form γ' -Fe₄N. The M_s value is in good agreement with that of bulk γ' -Fe₄N.
128 Using this technique, we were able to grow *a*-axis-oriented Fe₄N/MgO/Fe MTJ. The probable
129 method of formation of Fe₄N/MgO/Fe₄N MTJ was also discussed based on the XRD patterns.
130 In the *M-H* curve of the MTJ structure measured at 280 K, a two-step hysteresis loop was
131 observed, suggesting that two ferromagnetic layers were separated by a 1-nm-thick MgO
132 barrier layer.

133

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173 **Figure captions**

174

175 Figure 1 θ -2 θ XRD patterns of samples obtained after (a) 0, (b) 8, (c) 15, (d) 25 and
176 (e) 30 min after supplying Fe(30 nm)/MgO with Fe and N. (f) θ -2 θ XRD pattern obtained
177 after 60 min after supplying Fe(7 nm)/MgO with Fe and N. (g) θ -2 θ XRD pattern from N
178 supply after 60 min on Fe(7 nm)/MgO. Inserts show the RHEED patterns obtained at each
179 growth stage.

180

181 Figure 2 Schematic illustrations of (a) α -Fe on MgO(001) and (b) γ' -Fe₄N on
182 Fe/MgO(001). RHEED observation was performed along the [100] azimuth of MgO.

183

184 Figure 3 M - H curve of the γ' -Fe₄N(80 nm) layers on MgO measured at 280 K with H
185 parallel to the sample plane.

186

187 Figure 4 θ -2 θ XRD patterns of (a) before and (b) after the growth of MTJ. (a) and (b)
188 for MgO(1 nm)/Fe(100 nm), and Fe₄N/MgO/Fe MTJ, respectively.

189

190 Figure 5 M - H curve of the Fe₄N/MgO/Fe MTJ measured at 280 K with H parallel to
191 the sample plane.